HIDEN
ANALYTICAL

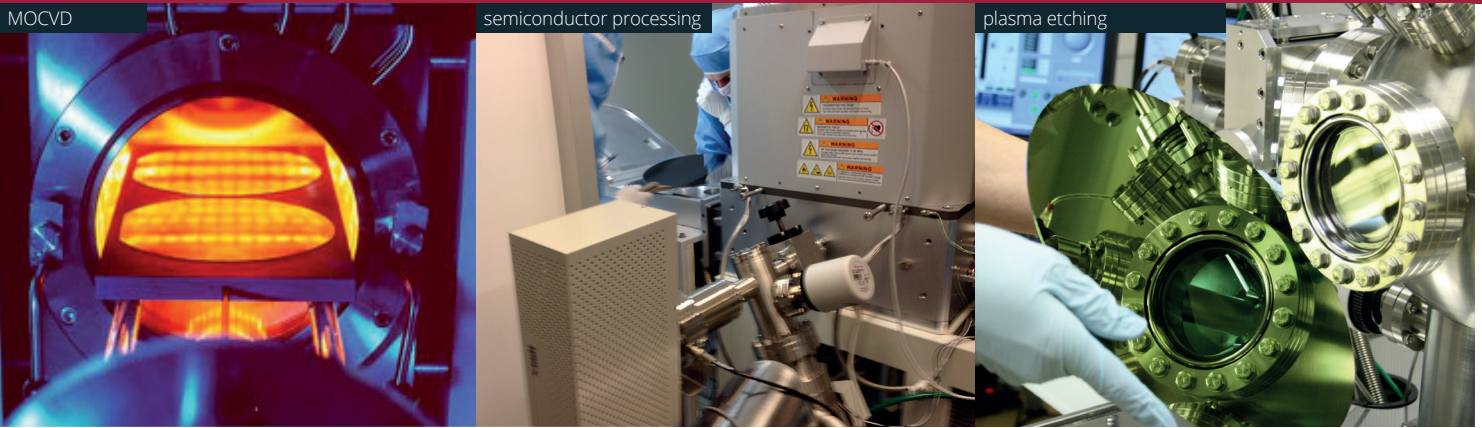# High Performance Mass Spectrometers

▸ **For Vacuum and Semiconductor Process Monitoring**

Detailed product information / introduction

MOCVD

semiconductor processing

plasma etching

Applications:

▶ CVD/MOCVD
▶ PECVD
▶ ALD
▶ Sputtering
▶ Vacuum coating
▶ Plasma etching
▶ MBE

Key Features

▶ **Robustness** and **stability** for permanent process monitoring

▶ Versatile systems for **different** process **pressure ranges**

▶ **Precision** analyses of residual gases, detection limit to 2×10^{-15} mbar

▶ Customised systems available

▶ Communication interfaces for external data analysis in real time

## PC Software for process monitoring and control:

iRGA

This newly developed LabVIEW®-based software allows a very straightforward analysis of frequently observed residual gases. The visual interface displays measured partial pressures in real time and indicates critical parameters in colour code. Trips can be set to send alarms via the internal I/O system or to external devices.
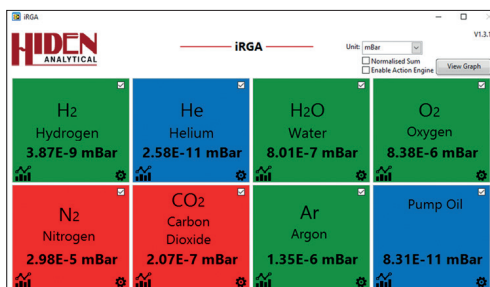
MASsoft

Hiden's MASsoft is a comprehensive software program giving access to trend view, histogram and peak profile modes. The user can set up scan sequences mixing the different modes and customising the scan parameters with additional statistical analysis functions available.


RGA Tablet mode
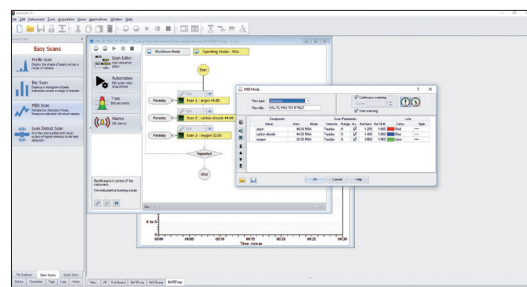

MASsoft Professional – overview

Process and Residual Gas Analyser (HPR-30 system)

Hiden's HPR-30 system is a gas analyser optimised for the analysis of gases and vapours in vacuum processes and vacuum diagnostics.

▶ Direct process analysis through the pressure range 10^{-4} mbar to 1 mbar and extendable to 1000 mbar

▶ Unique sampling probe orifice can be extended directly into the process region for optimised response and sensitivity

▶ Sensitivity to 100 parts-per-billion as standard and 5 parts-per-billion with optional triple stage mass filter

▶ Integrated high conductance valve option for residual gas analysis at chamber pressures < 10^{-4} mbar

▶ Pneumatic valve control option for automatic sampling operation with manual override and fail-safe interlock in case of over pressure or power failure

▶ Mass range is 200 amu as standard – with high mass range options to 300 amu, 510 amu and 1000 amu with triple stage mass filter

▶ Flexible configuration options including pole-mounted/cart integrated systems providing a portable vacuum diagnostics platform that is readily utilized across multiple vacuum chambers and process tools
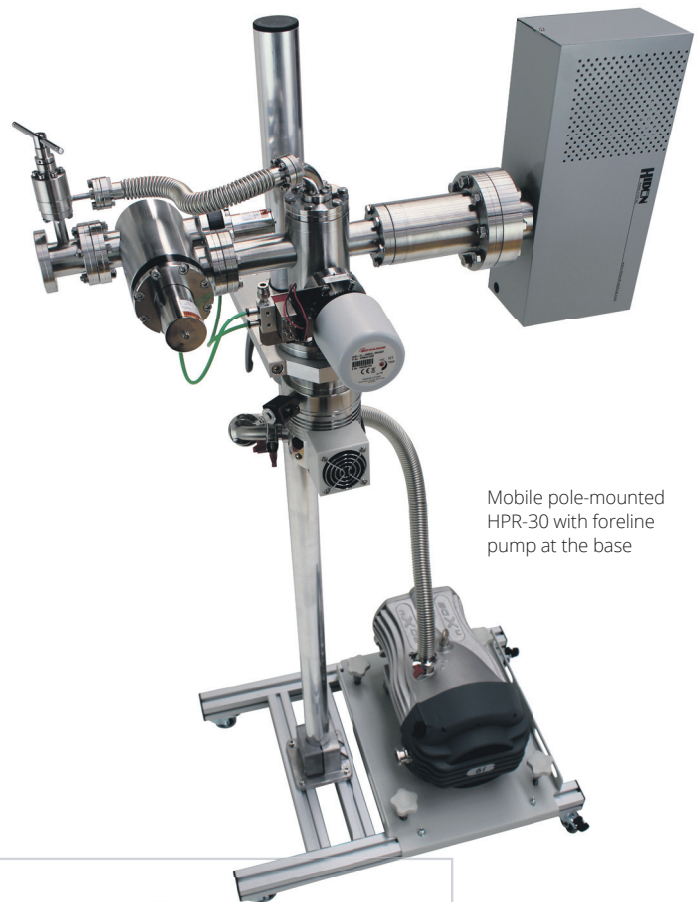
Mobile pole-mounted HPR-30 with foreline pump at the base
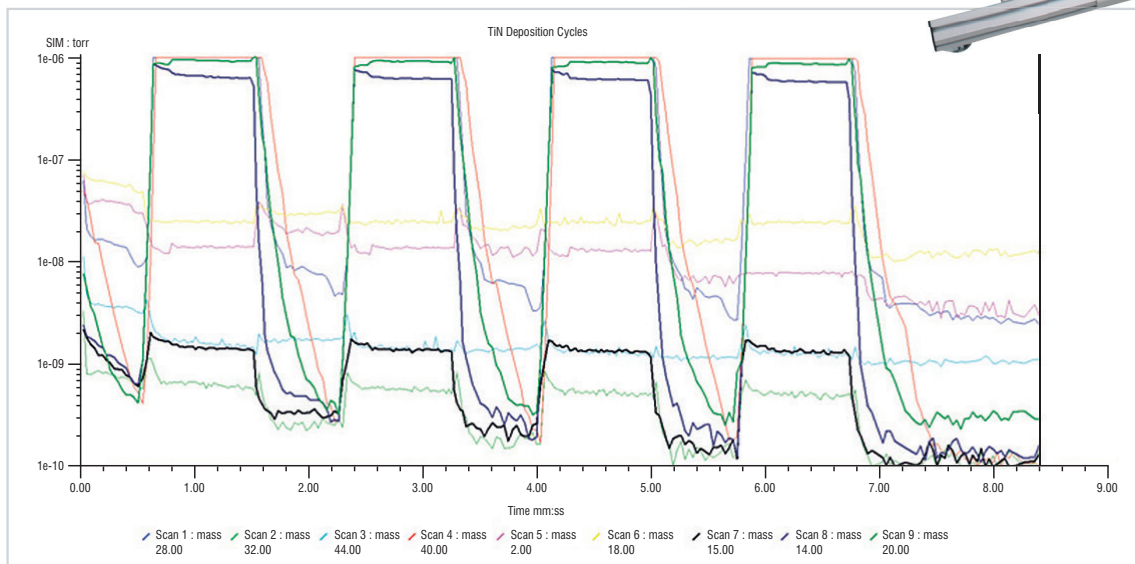
HPR-30 data from a TiN deposition process

Vacuum accessories and systems for RGA operation

HMT – High Pressure RGA

Hiden's HMT RGA system is a unique dual mode RGA that operates as a conventional RGA for vacuum diagnostics and monitoring at pressures of less than 10^{-4} mbar and can switch into a high pressure mode for process analysis at pressures up to 5×10^{-3} mbar without a requirement for differential pumping or a sampling system.
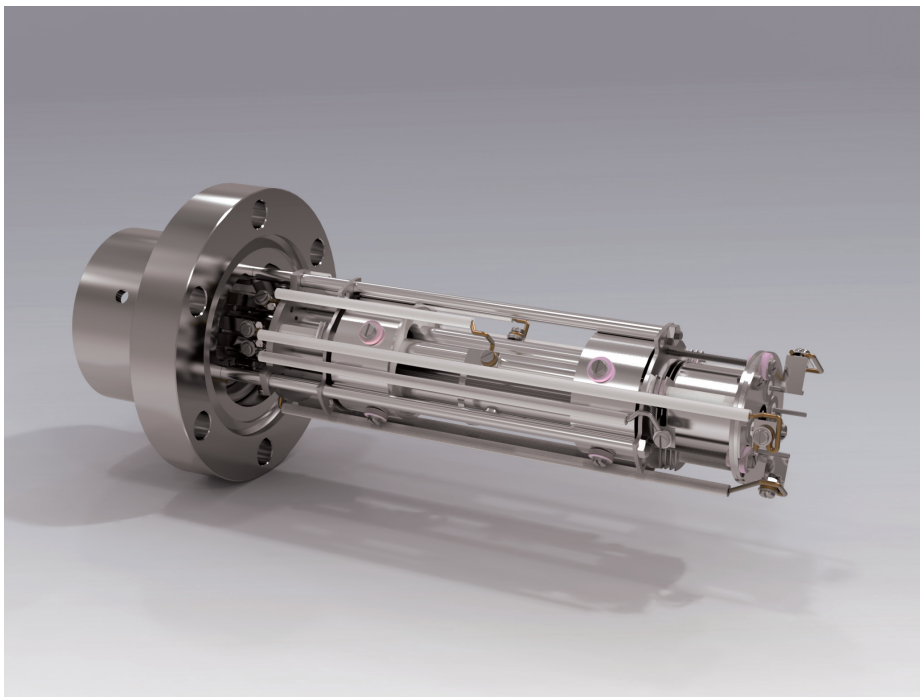
Key Features

▸ HMT mode for high pressure operation to 5×10^{-3} mbar

▸ RGA mode for high sensitivity operation to 2×10^{-13} mbar

▸ 100 amu mass range

▸ stability better than +/- 1% over 24 hours

▸ fast access mixed mode scanning

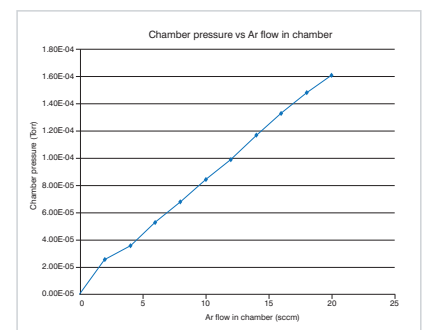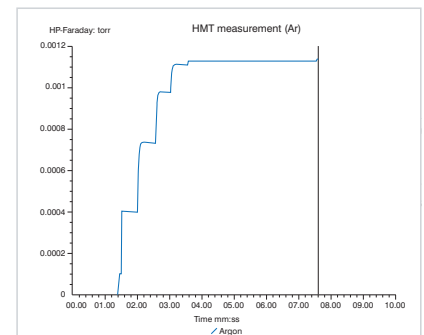▸ real-time background subtraction

Vacuum process sampling

Hiden offers vacuum sampling accessories and components that are available as bolt-on low cost modules or part of an integrated system.

Vacuum accessories for process monitoring:

▸ Sample lines and options for sampling over a range of process pressures

▸ RGA gauge housing with ports for vacuum pumping, pressure gauge and sampling line

▸ RGA gauge head sampling tube with aperture for sampling
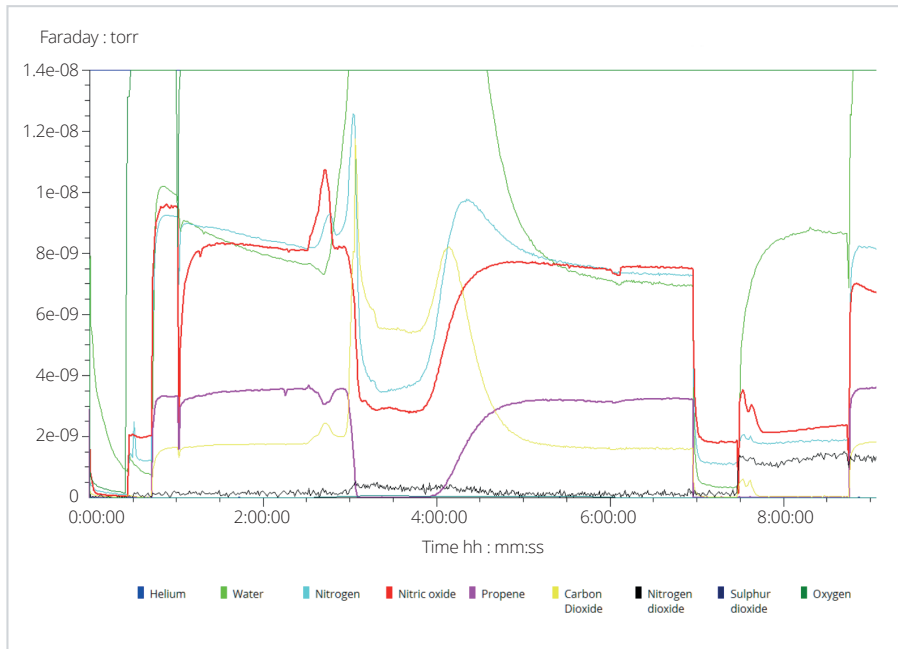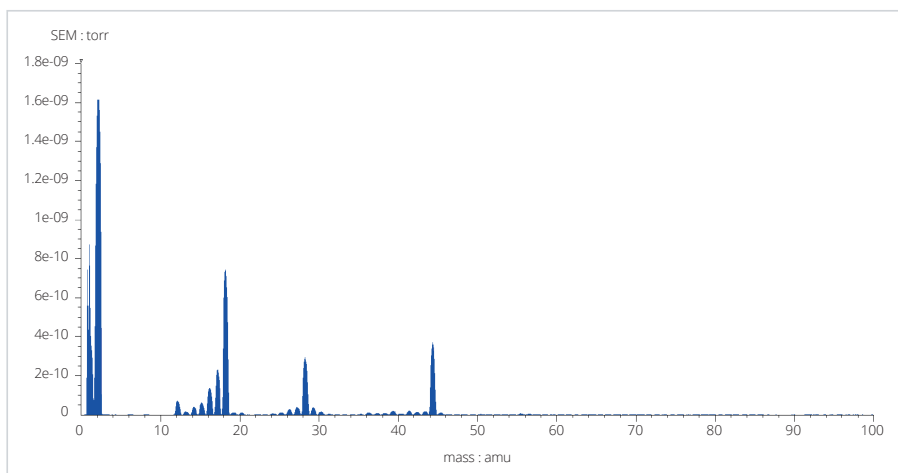
▸ UHV turbomolecular pump system

HMT

HMT Analyser measuring Argon in the process chamber

RGA - Residual Gas Analysis

Faraday : torr

Legend: Helium, Water, Nitrogen, Nitric oxide, Propene, Carbon Dioxide, Nitrogen dioxide, Sulphur dioxide, Oxygen

Process analysis – multiple species monitored over 8 hours

- ▶ Quadrupole mass spectrometers provide for fast sensitive measurement of all vacuum residuals from light elements, hydrogen and helium through to volatile organic species.

- ▶ The RGA gauge head protection accessory is recommended for applications where the RGA can be used pre-process, placing the analyser out of the line of sight of potentially harmful condensing species and isolating it when the processing at higher pressures begins.

- ▶ Hiden's range of residual gas analysers are based on high performance quadrupole mass spectrometers, and provide a unique window into the vacuum environment for contamination monitoring, leak detection, and for analysis of species of interest within the vacuum chamber.
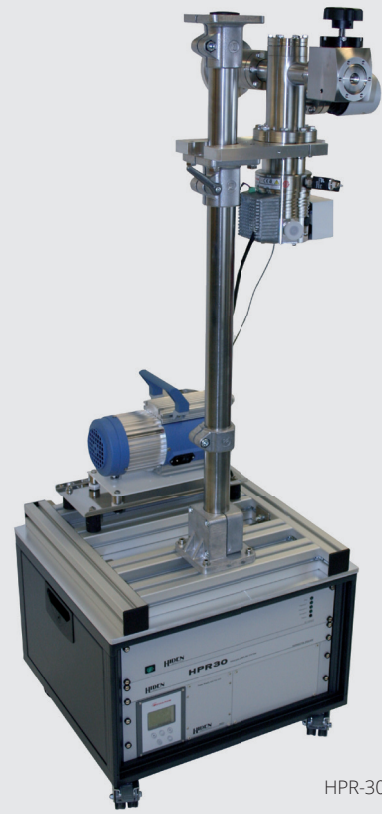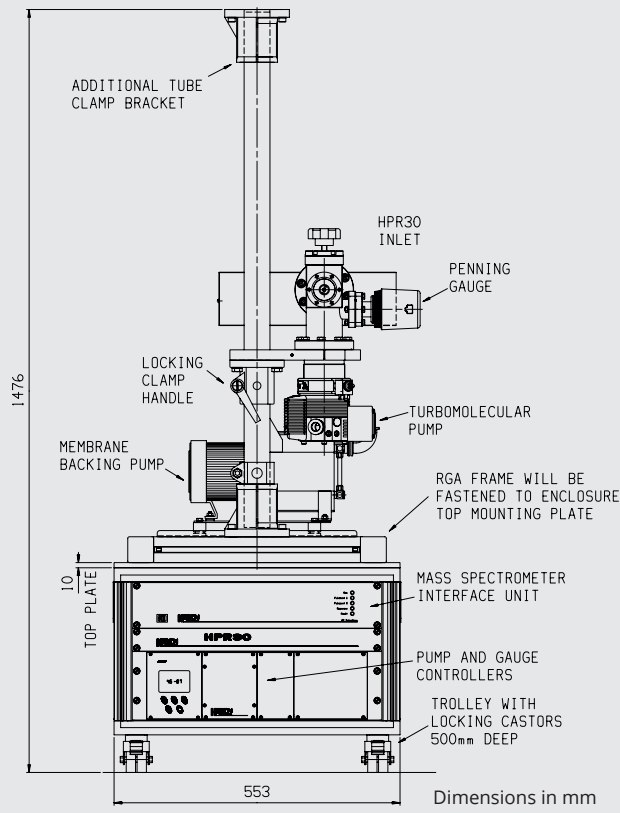

SEM : torr

Residual gas spectrum of a clean chamber at UHV

RGA analyser gauge
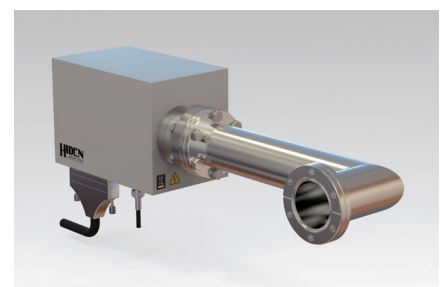
RGA gauge head protection accessory – a UHV housing with 90 degree elbow (RAH-9 housing).

Residual Gas Analysers for vacuum process monitoring

| ITEM	DESCRIPTION	PARTCODE
	Vacuum Process Sampling Systems	
HPR-30	HPR-30 Vacuum process sampling system, including HAL 201 RC mass spectrometer with Faraday and Electron Multiplier Detectors. Mass range 200 amu. Process pressure range for sampling: 1 mbar to 10^{-4} mbar. The sampling pressure range may be extended with special options. The HPR-30 system includes: ▷ Re-entrant probe with user changeable sampling orifice ▷ Vacuum system – all dry turbomolecular pump set with total pressure gauge and safety interlock for protection of the mass spectrometer in case of over pressure	305300
HPR-30 CART	HPR-30 Vacuum process sampling system mounted on a compact mobile cart with flexible height adjustment for coupling to multiple chamber types	305320
QC 2.1	Extended mass range to 300 amu with triple filter mass spectrometer	305021
QC 2.2	Extended mass range to 510 amu with triple filter mass spectrometer	301200
QA 1.0	Extended mass range to 1000 amu with triple filter mass spectrometer	301300
LKV-30	Extended sampling pressure range up to 1000 mbar Process sampling leak valve with flexible stainless steel bellows and DN-35-CF flanged coupling	305325
VS 3.3	Pneumatic valve option with automatic control module	303603
	Vacuum Process Sampling Accessories And Components	
RAH-9	RGA analyser housing with 90° elbow	202110
HTM	HPR-30 UHV Manifold bakeout heater set	303330
VPA-1	1 m long sampling line for optimum conductance for sampling the pressure regime: 10^{-4} mbar to 10^{-2} mbar	303331
VPA-2	2 m long sampling line for optimum conductance for sampling the pressure regime: 10^{-2} mbar to 1 mbar	303332

Dimensions in mm

ADDITIONAL TUBE CLAMP BRACKET
HPR30 INLET
PENNING GAUGE
LOCKING CLAMP HANDLE
TURBOMOLECULAR PUMP
MEMBRANE BACKING PUMP
RGA FRAME WILL BE FASTENED TO ENCLOSURE TOP MOUNTING PLATE
MASS SPECTROMETER INTERFACE UNIT
PUMP AND GAUGE CONTROLLERS
TROLLEY WITH LOCKING CASTORS 500mm DEEP
TOP PLATE
1476
10
553

HPR-30 Cart

ITEM	DESCRIPTION	PARTCODE
High Pressure Residual Gas Analysers		
HMT 100	High pressure RGA system 100 amu Faraday Detector Minimum detectable partial pressure 2×10^{-11} mbar Maximum operating pressure 5×10^{-3} mbar	**151100**
HMT 101	High pressure RGA system 100 amu Faraday and Electron Multiplier Detector Minimum detectable partial pressure 2×10^{-13} mbar Maximum operating pressure 5×10^{-3} mbar	**151101**
Residual Gas Analysers		
HAL0 100 RC	RGA sytem 100 amu Faraday Detector Minimum detectable partial pressure 2×10^{-11} mbar Maximum operating pressure 1×10^{-4} mbar	**141100**
HAL 201 RC	RGA sytem 200 amu Faraday and Electron Multiplier Detector Minimum detectable partial pressure 5×10^{-14} mbar Maximum operating pressure 1×10^{-4} mbar	**144100**

Hiden**APPLICATIONS**

Hiden's quadrupole mass spectrometer systems address a broad application range in:

GAS ANALYSIS

- dynamic measurement of reaction gas streams
- catalysis and thermal analysis
- molecular beam studies
- dissolved species probes
- fermentation, environmental and ecological studies
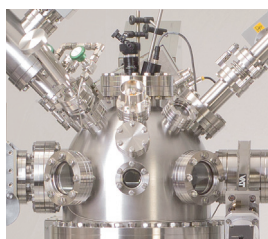
SURFACE ANALYSIS

- UHV TPD
- SIMS
- end point detection in ion beam etch
- elemental imaging – 3D mapping

PLASMA DIAGNOSTICS

- plasma source characterisation
- etch and deposition process reaction kinetic studies
- analysis of neutral and radical species

VACUUM ANALYSIS

- partial pressure measurement and control of process gases
- reactive sputter process control
- vacuum diagnostics
- vacuum coating process monitoring

Sales Offices:

We have sales offices situated around the globe. **Visit our website for further information.**